



Introduction to Nanotechnology and Nanoscience – Class#3

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Outline

- Top-down Technologies
- Semiconductor & Silicon
- MOSFET
- HW#1

- (some materials from Professors Lydia Sohn & Tsu-Jae King Liu)



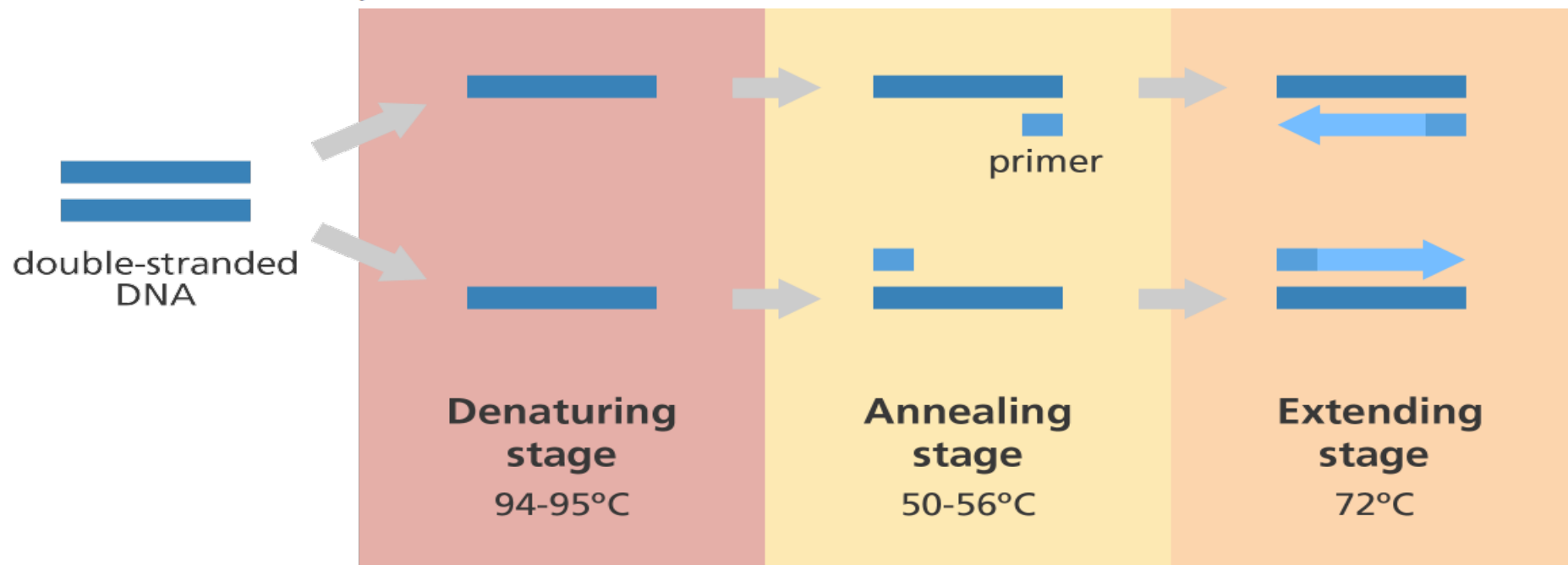
Announcements

- A fairly “good” textbook:
 - Nanophysics & NanoTechnology, Edward Wolf
Wiley-VCH, 2006 (Amazon.com)

Functional Integration of PCR Amplification and Capillary Electrophoresis in a Microfabricated DNA Analysis Device

Adam T. Woolley,[†] Dean Hadley,[‡] Phoebe Landre,[‡] Andrew J. deMello,^{†,§} Richard A. Mathies,^{*,†} and M. Allen Northrup[‡]

Department of Chemistry, University of California, Berkeley, California 94720, and Microtechnology Center, L-222, Lawrence Livermore National Laboratory, Livermore, California 94551

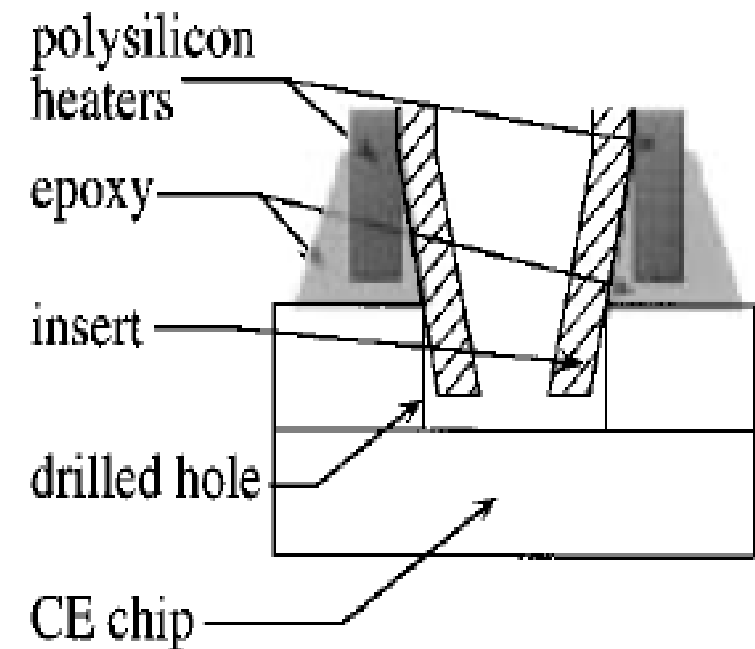


News Releases

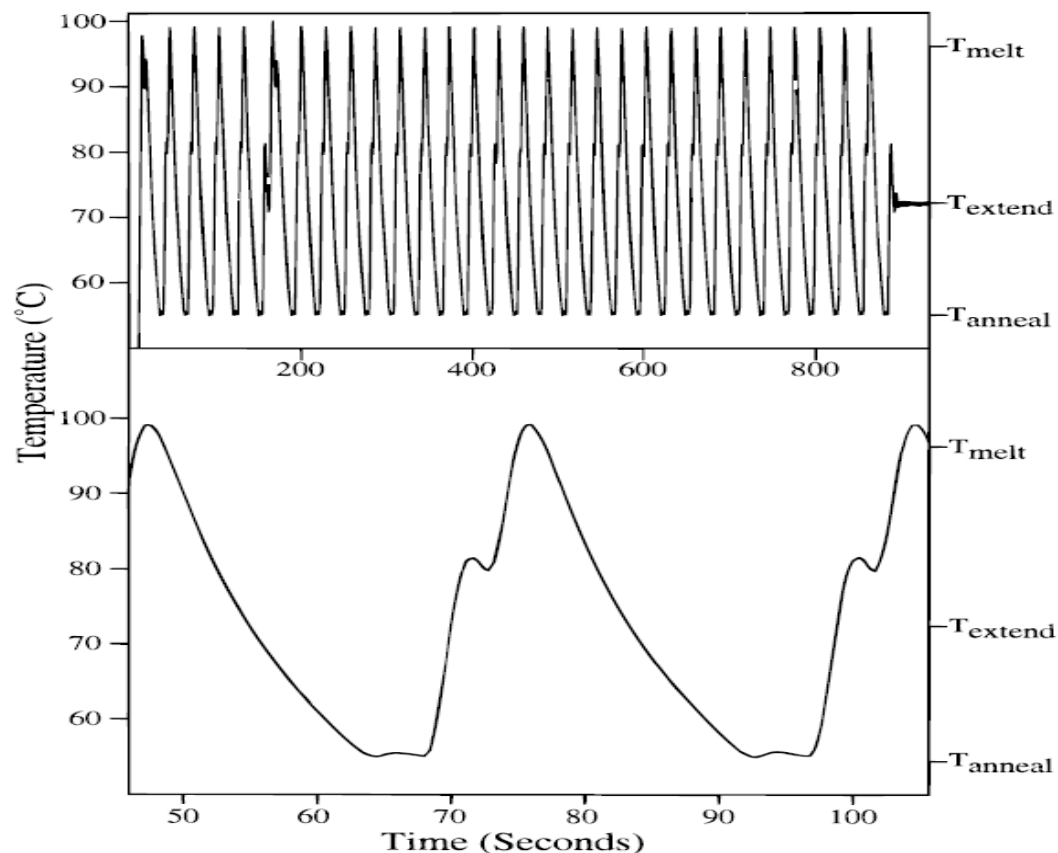
Cepheid Receives Emergency Use Authorization from FDA for Rapid SARS-CoV-2 Test

First Rapid, Point-of-Care and Near-Patient Molecular Test for Detection of Virus that Causes COVID-19

SUNNYVALE, Calif., March 21, 2020 /[PRNewswire](#)/ -- Cepheid today announced it has received Emergency Use Authorization (EUA) from the U.S. Food & Drug Administration (FDA) for Xpert[®] Xpress **SARS-CoV-2**, a rapid molecular diagnostic test for qualitative detection of **SARS-CoV-2**, the virus causing COVID-19. The test has been designed to operate on any of Cepheid's more than 23,000 automated GeneXpert[®] Systems worldwide, with a detection time of approximately 45 minutes.



Liwei Lin, U



Cepheid



Cepheid headquarters in Sunnyvale

Corporate status

Cepheid was founded in March 1996 by Thomas Gutshall, Bill McMillan, Dr. Kurt Petersen, Dr. Greg Kovacs, Steven Young and Dr. Allen Northrup.

The company went public in 2000.^[5] The initial public offering was June 21, 2000 at US\$6 per share. Cepheid stock was listed on the Nasdaq under the ticker symbol CPHD until it was acquired by Danaher in 2016.^[26]

During the 2001 anthrax attacks, U.S. federal agencies contracted with Cepheid to track the anthrax.^{[7][5]}

During the COVID-19 pandemic, Cepheid began the development of a CRISPR-based diagnostic test for the SARS-CoV-2 (then called "2019-nCov") virus.

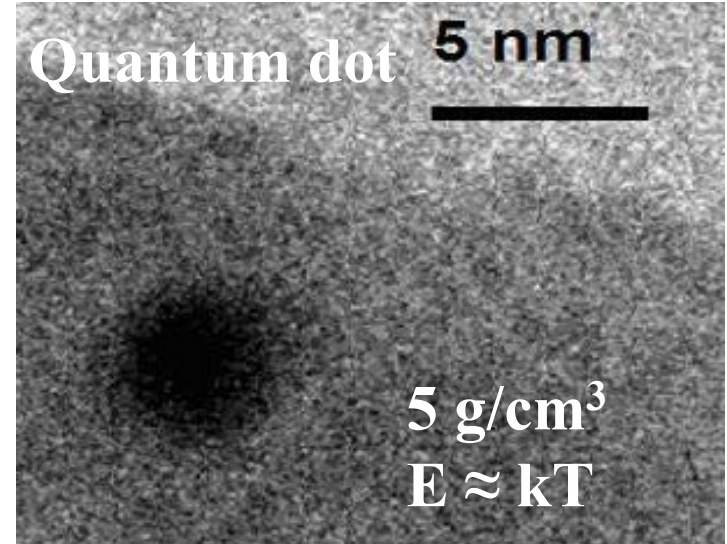
Type	<u>Subsidiary</u>
Industry	<u>Biotechnology</u> <u>Medical devices</u>
Founded	March 1996
Headquarters	<u>Sunnyvale, California, U.S.</u>



Quantum Mechanics



vs

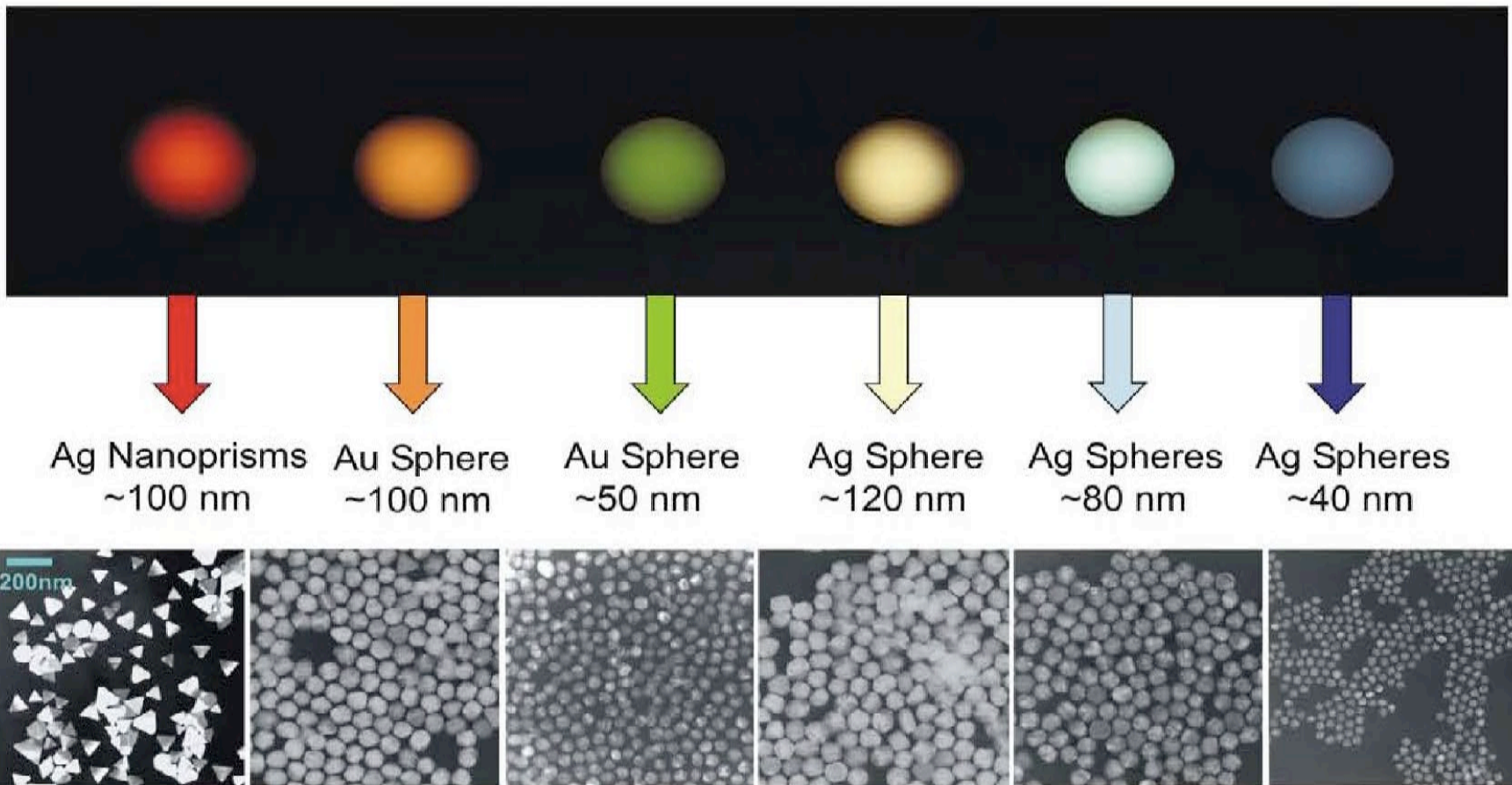


$$\lambda = \frac{\hbar}{\sqrt{2mE}}; \quad \hbar \sim 1 \times 10^{-34} \text{ J-s}$$



Rayleigh Light-Scattering of Nanocrystals

Shape, Size, and Composition Matter



* The scale bar is the same for all the images.



Optical Absorption

Gold Building Blocks

Atoms:
colorless, 1 Å

Gold clusters:
orange, nonmetallic,
<1 nm

Gold nanoparticles:
3–30 nm, red, metallic,
“transparent”

Gold particles:
30–500 nm
metallic, turbid,
crimson to blue

Bulk gold film

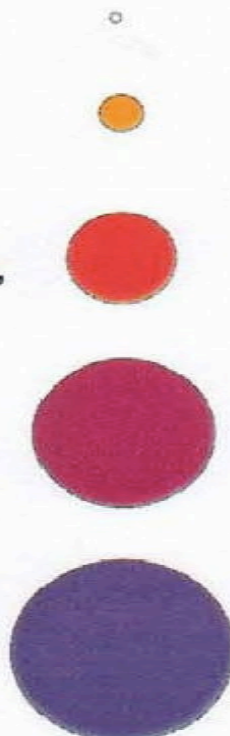


Figure 1. Gold building blocks, from the atomic to the mesoscopic, and their changing colors.

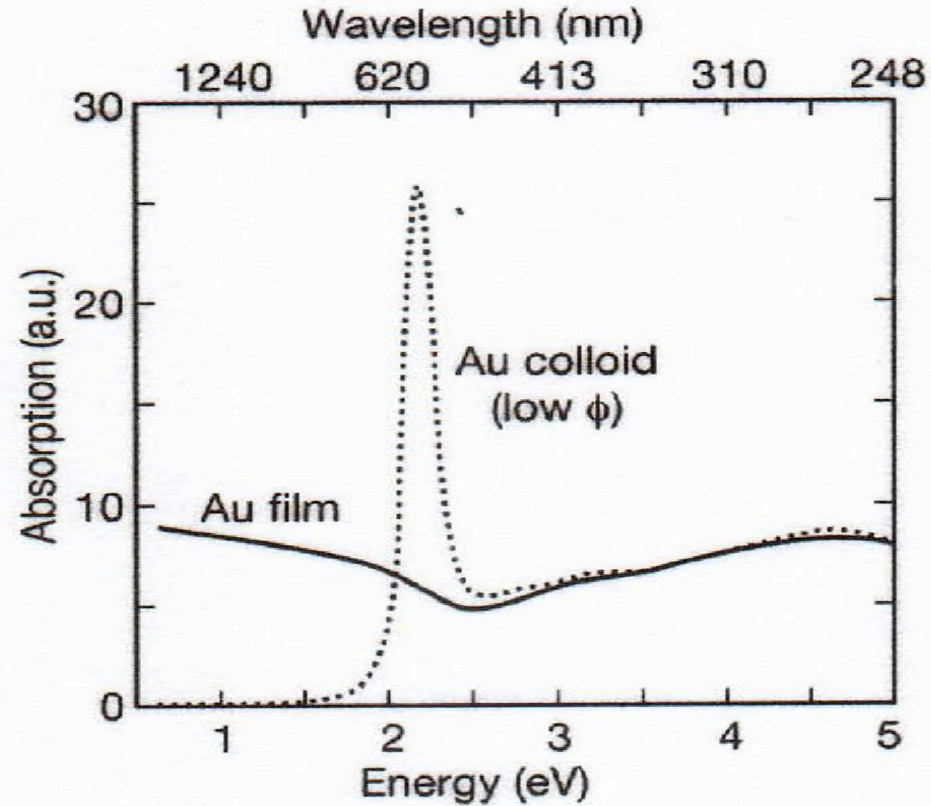
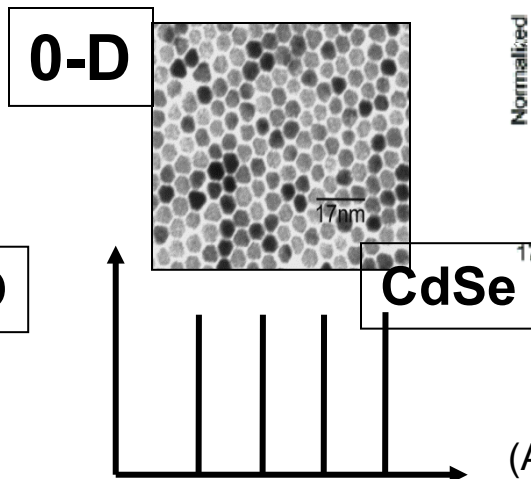
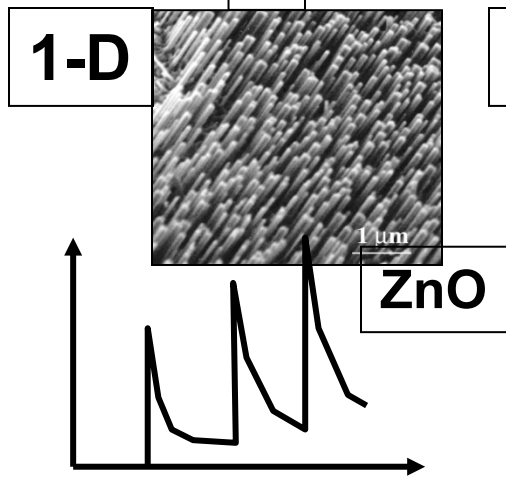
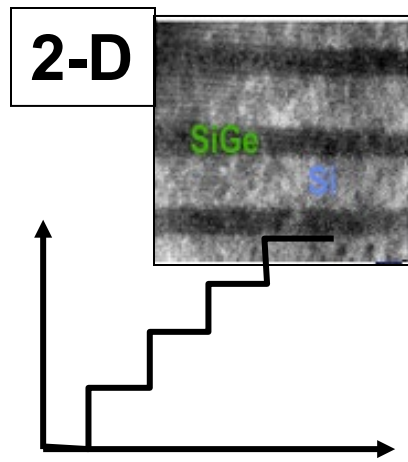
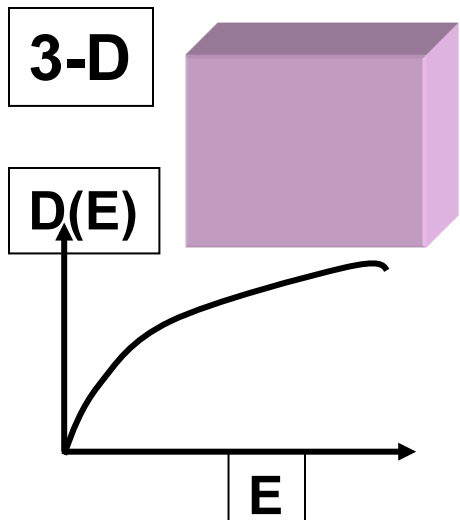


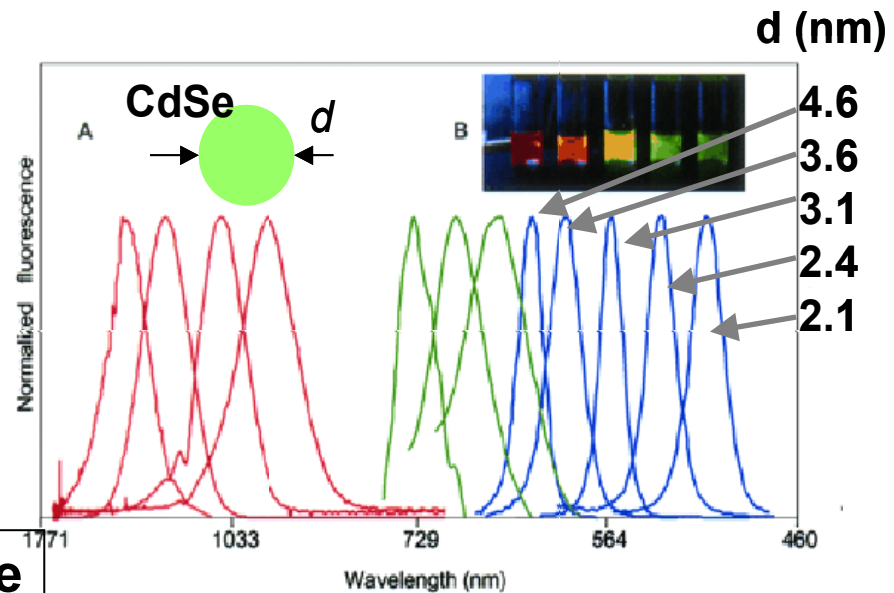
Figure 3. Absorption spectra of a gold nanocrystal film and a thin, bulk gold metal film of equivalent thickness. ϕ is the volume fraction of gold in the sample.



Effects of Confinement of Charge Carriers



**Example: CdSe quantum dots
Fluoresces vs. wavelength**



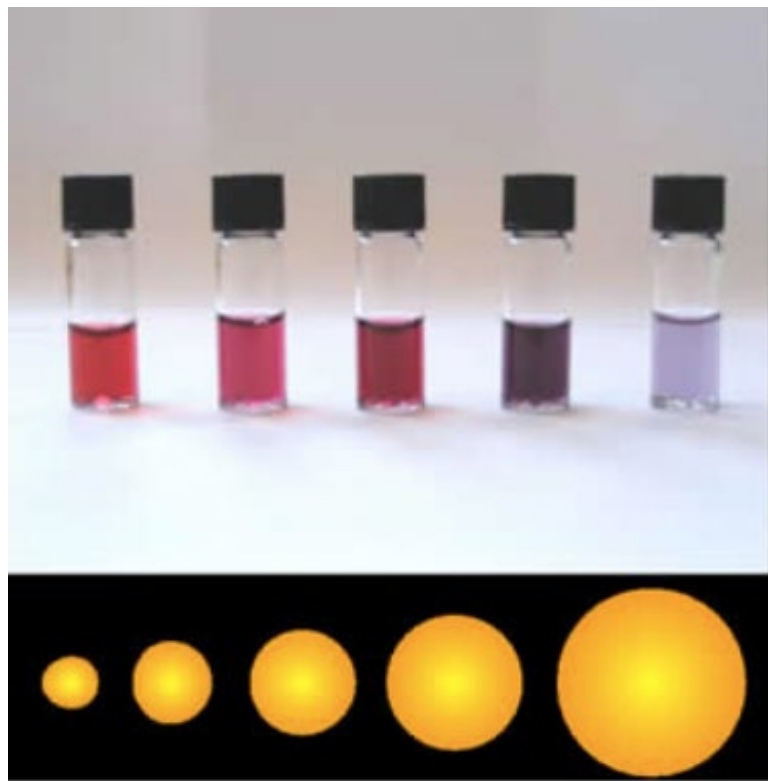
(Paul Alivisatos, UCB)

(After Arum Majumdar, UCB)



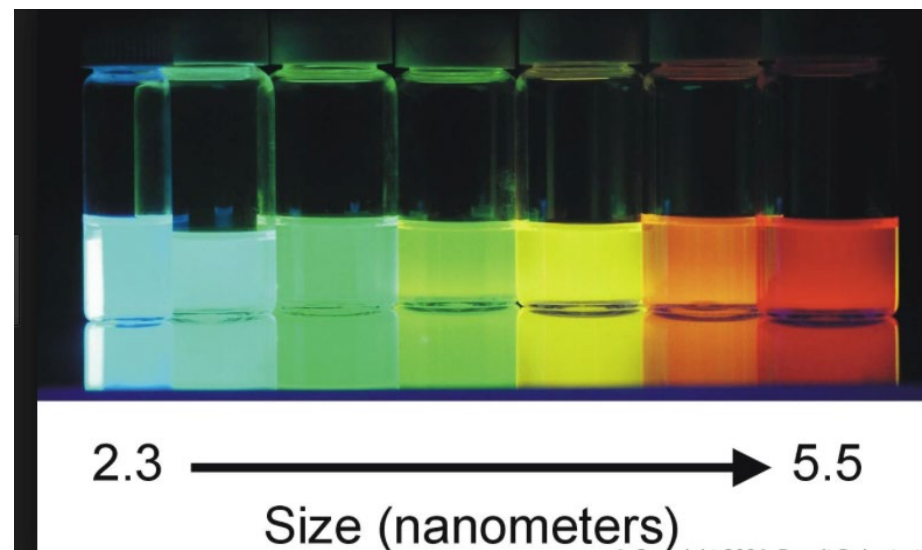
What's going on here?

Gold nanoparticles



CdSe quantum dots

vs.

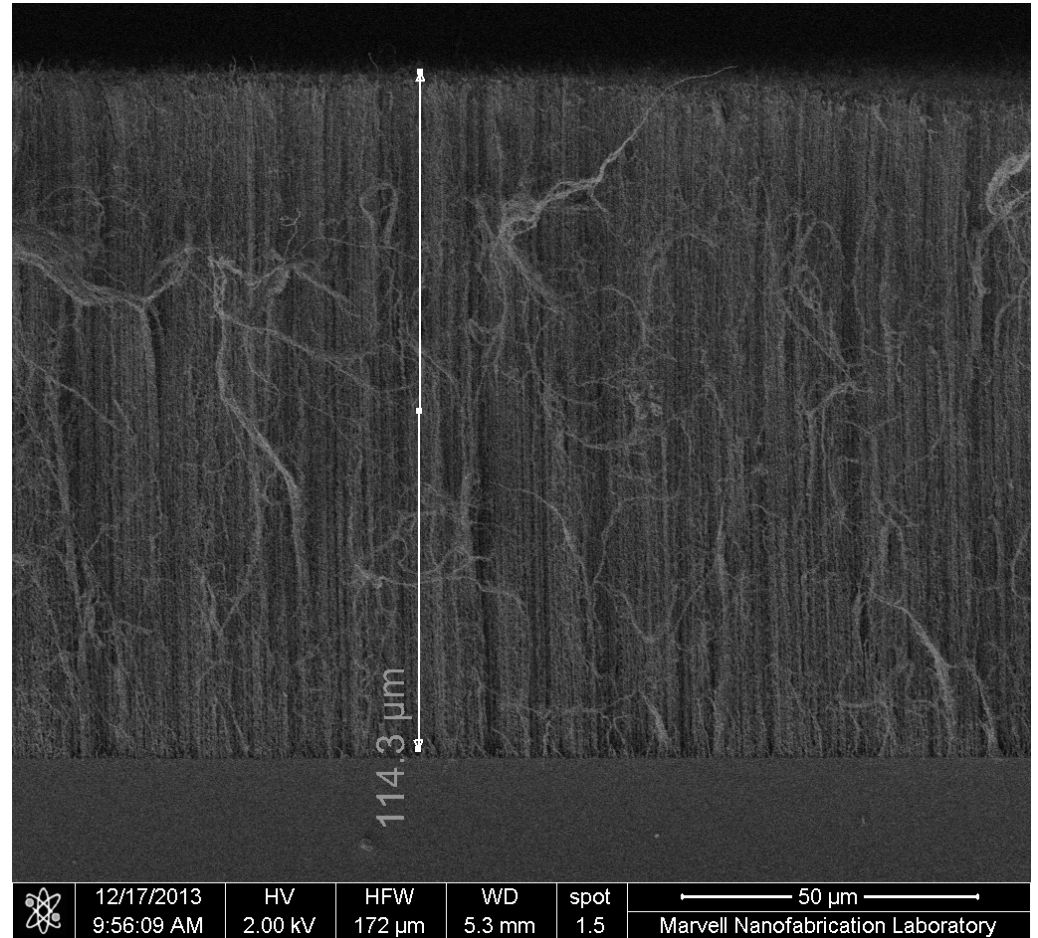




Aspect Ratio



VS





Electrical Properties: Tunneling Current

- At the nanometer scale, electrical insulators begin to fail to block current flow
- Quantum mechanical effect known as **tunneling**
- Tunneling current increases exponentially as the thickness of the insulator is decreased
- Tunneling is the basis of the scanning tunneling microscope and covalent chemical bonding

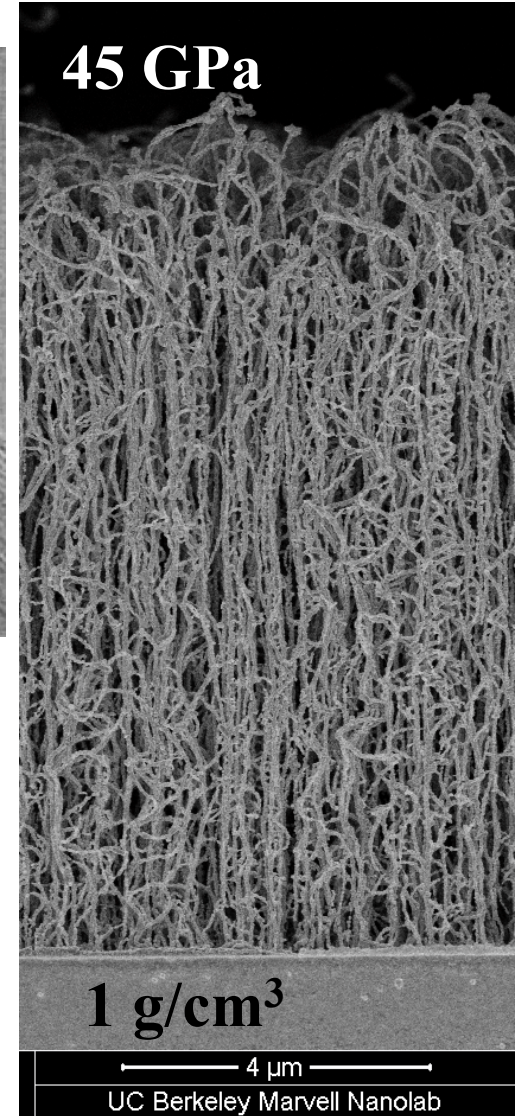
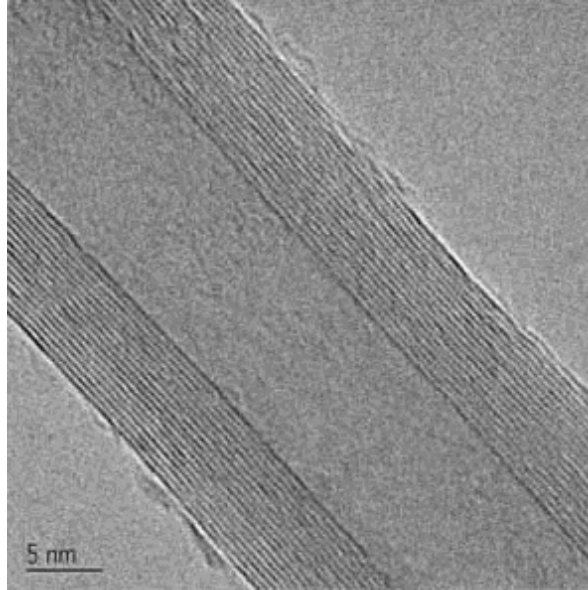


Strength-to-weight ratio



520 MPa
8 g/cm³

vs.



Pa/(kg/m³)

<http://www.owl.net.rice.edu/~biy/Selected%20papers/01TAPhys.pdf>

http://cnx.org/contents/f3abd155-e65d-4155-bd2c-9b435b6d2f6a@4/Carbon_Nanomaterials



Nanotube Composite

{ TENNIS }
{ TEAM PRO }

(What's hot ?) (Babolat in your country) (Technology) (Player profiles) (Tour players) (Press Release)



TENNIS RACKETS

CONTENDER / ACTIV

PASSION
Top-of-the-line

All products Contender / Activ

VS Nanotube™ Power

VS Nanotube™ Drive

VS NCT Power

VS NCT Drive

VS NCT Control

COMPETITOR / PRO

COMPETITION
Performance objectives

All products Competitor/Pro

Pure Power Zylon™ used 360° ▲

Pure Drive Zylon™ used 360°

Pure Control Zylon™ used 360°

Pure Drive Team

Pure Control Team ▼

CHALLENGER

RECREATION
Priority on enjoyment

All products Challenger

Soft Power ▲

Soft Drive

Contest Serie 1

Contest Serie 2

Classic Ti ▼

JUNIOR

A range designed to allow the progressive learning of junior players.

Pure Drive Zylon™ used 360° Jr

Pure Junior

Roddick Junior 145

Roddick Junior 140

Ballfighter

VS Nanotube™ Power

Power thanks to a larger sweetspot.

WOOFER
DUAL



- Carbon Nanotube™ Stabilizers increases torque (+50%) and flex (+20%) resistance.
- Dual Woofer, 5 times more shock absorbing than conventional grommet.

PASSION COMPETITION RECREATION

Power Control

HeadSize	750 cm ² / 116 sq.in
Weight	245 gr / 8.6 oz
Composition	Carbon Nanotube™/ High modulus graphite
Grip	Air Touch Grip





Size-Dependent Properties

At the nanometer scale, properties become **size dependent!**

For example,

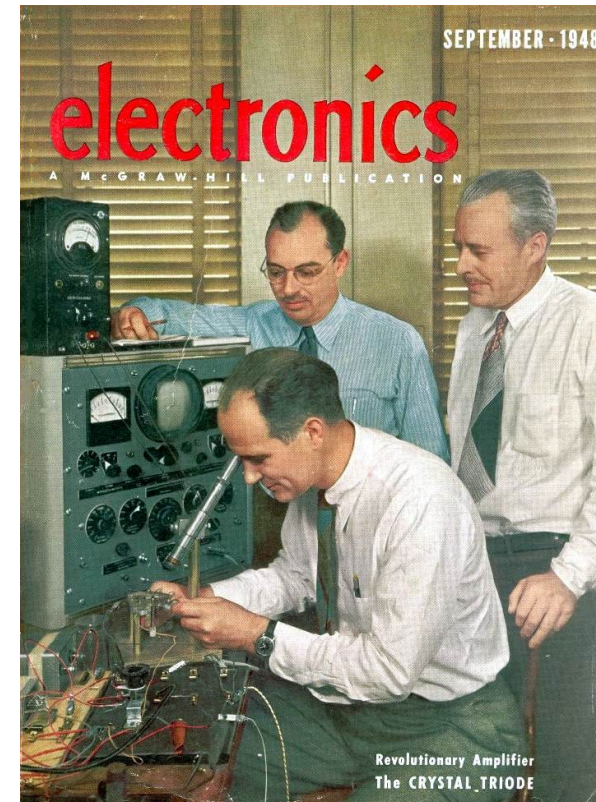
- Thermal properties — melting temperature
- Mechanical properties — adhesion, capillary forces
- Optical properties — absorption and scattering of light
- Electrical properties — tunneling current
- Magnetic properties — superparamagnetic effect

New properties enable new applications



Invention of the Transistor

The Greatest Motivation



http://www.bellsystemmemorial.com/belllabs_transistor.html

The first transistor was invented in 1947 by Bardeen, Brattain, and Shockley at Bell Laboratories. BBS won the Nobel Prize in 1956



The Ever-Shrinking Transistor



1st Transistor
1947

Bell Lab -
Bardeen, Brattain,
Shockley

TI

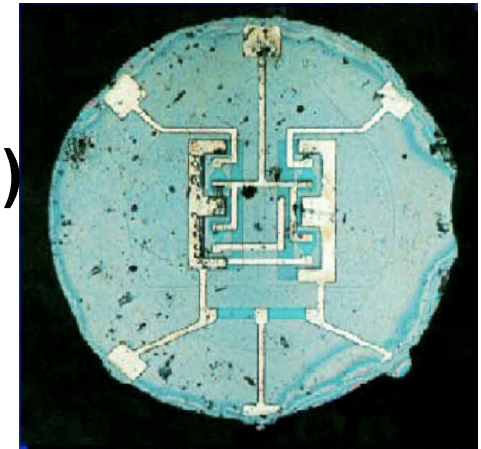
Jack Kilby
Nobel Prize @2000



1st Integrated Circuit (IC)
1958

Fairchild

Robert Noyce

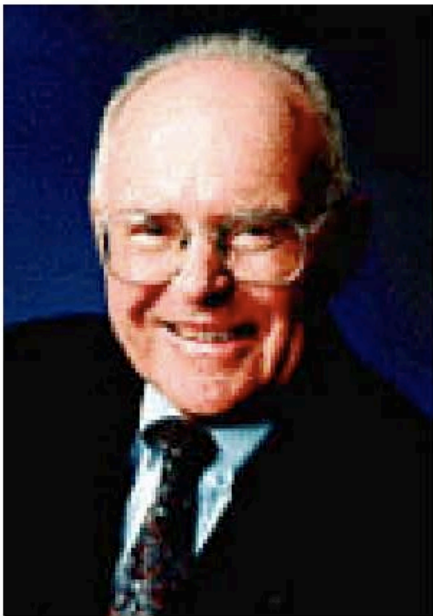


1st Planar IC
1961

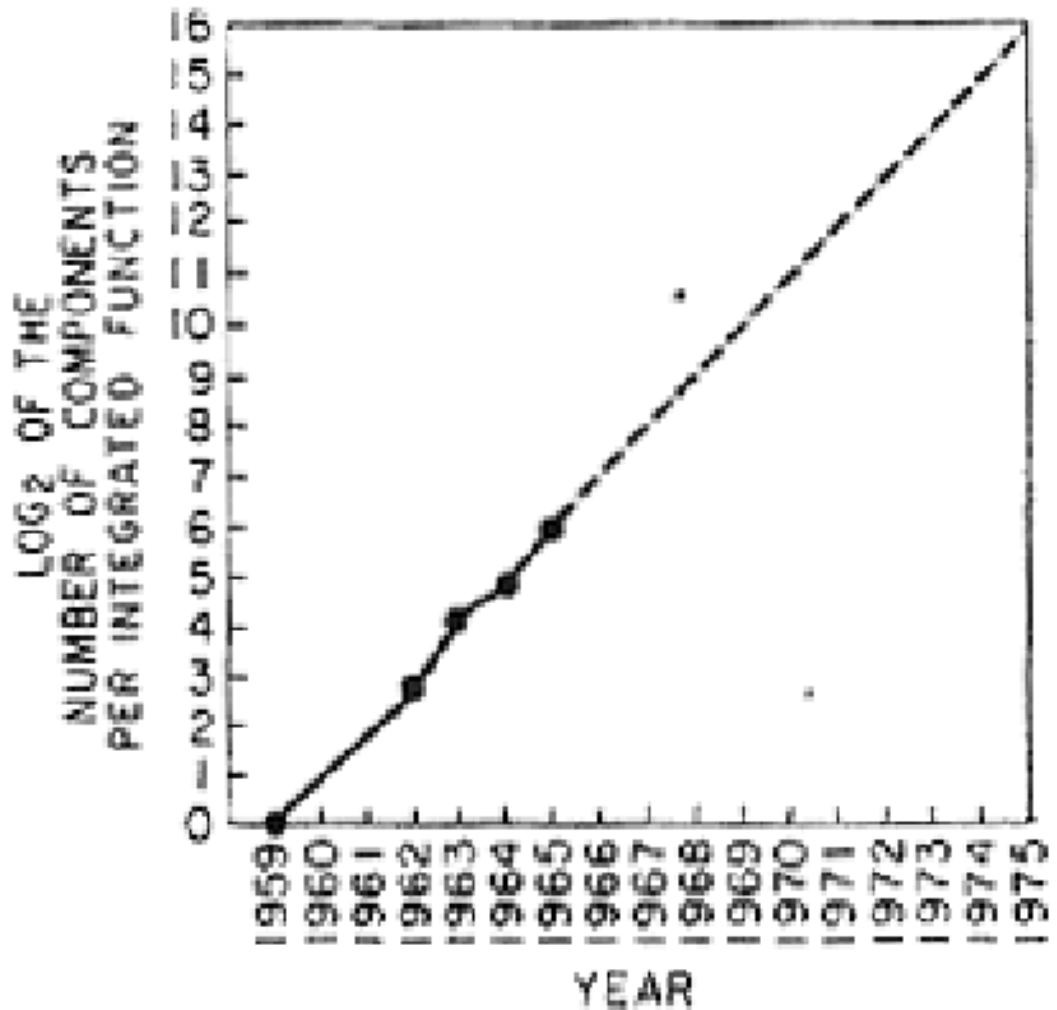


“Moore’s Law”

Not a Law, Just a Roadmap!



**Intel Co-Founder
Gordon E. Moore**



Moore, Electronics **38**, 1965

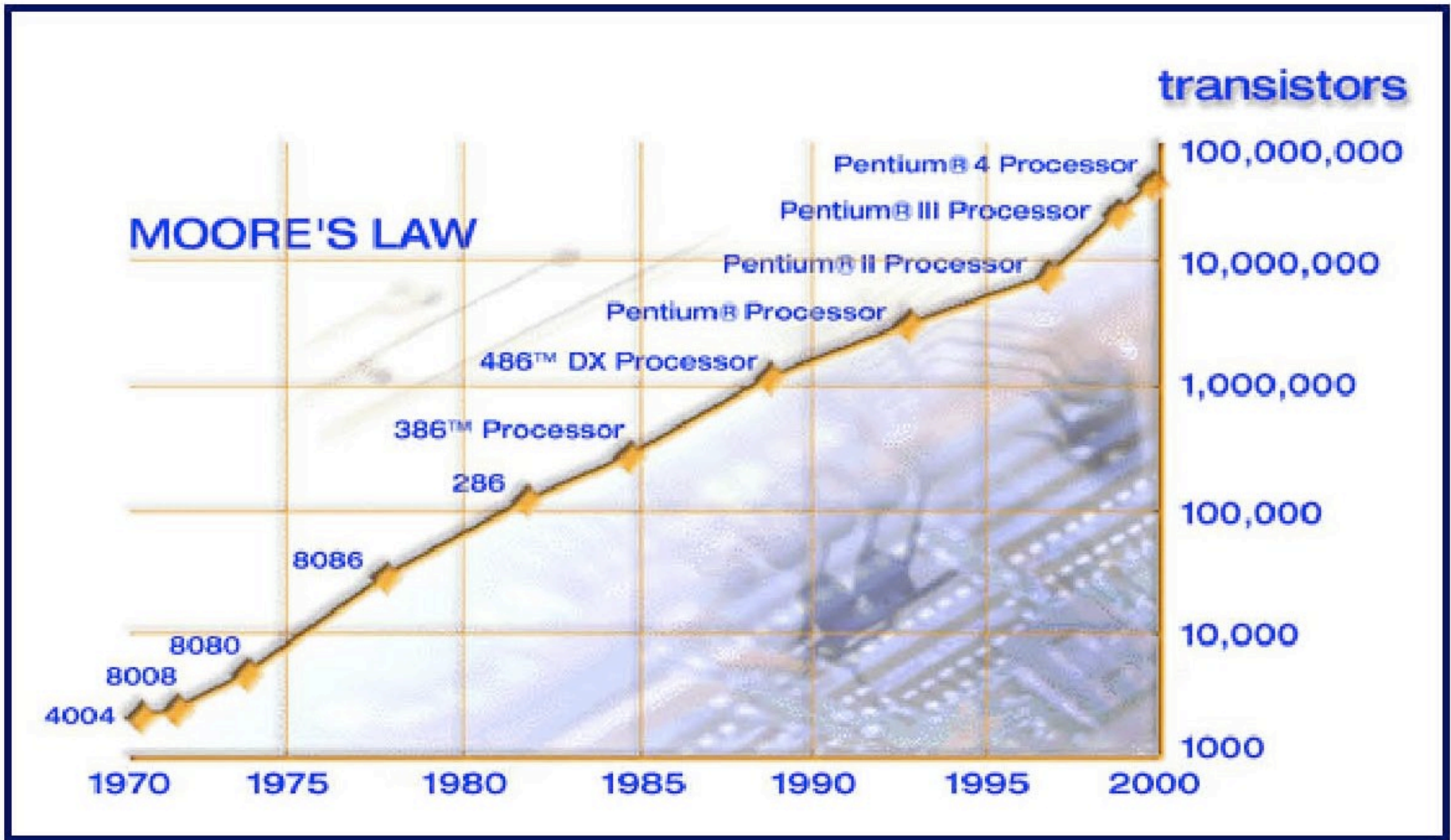


640K ought to be enough for anybody...

Bill Gates, 1981

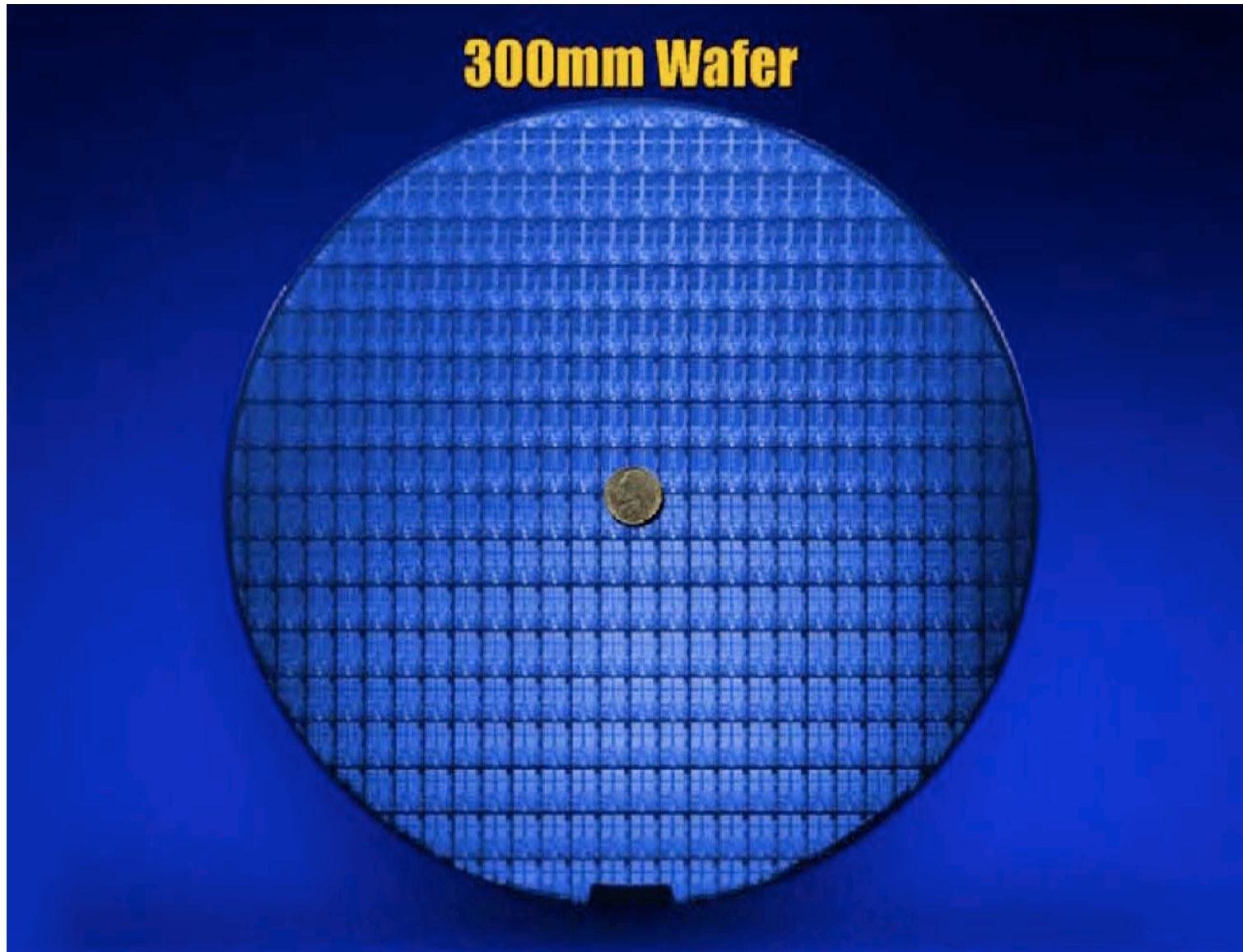


Where Are We Now?

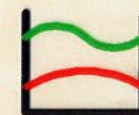
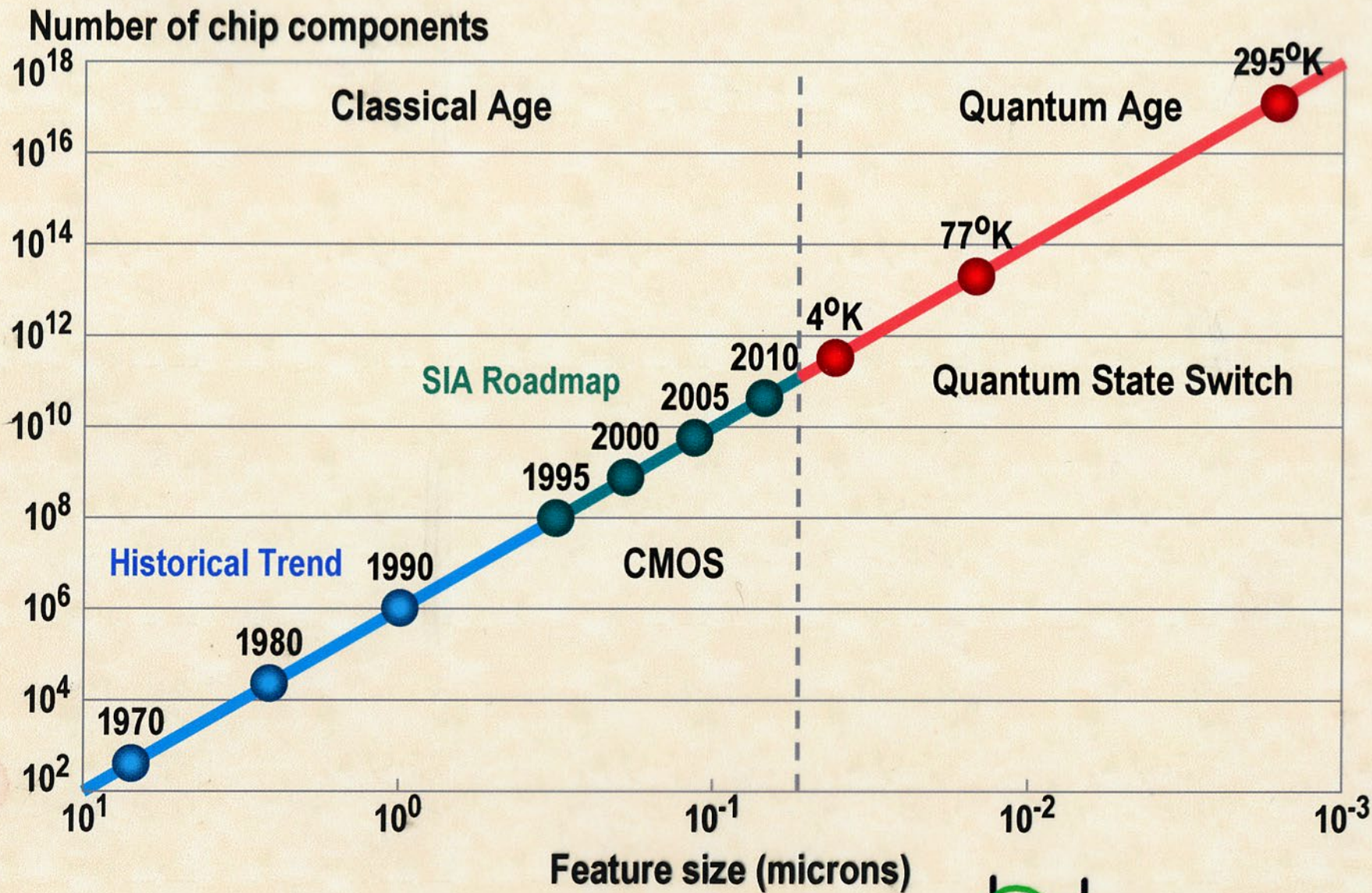


No exponential is forever...but we delay "Forever."

G. Moore, 2003



Scaling of electronic devices





Nanofabrication

- Top Down:

“Chisel” away material to make nanoscale object

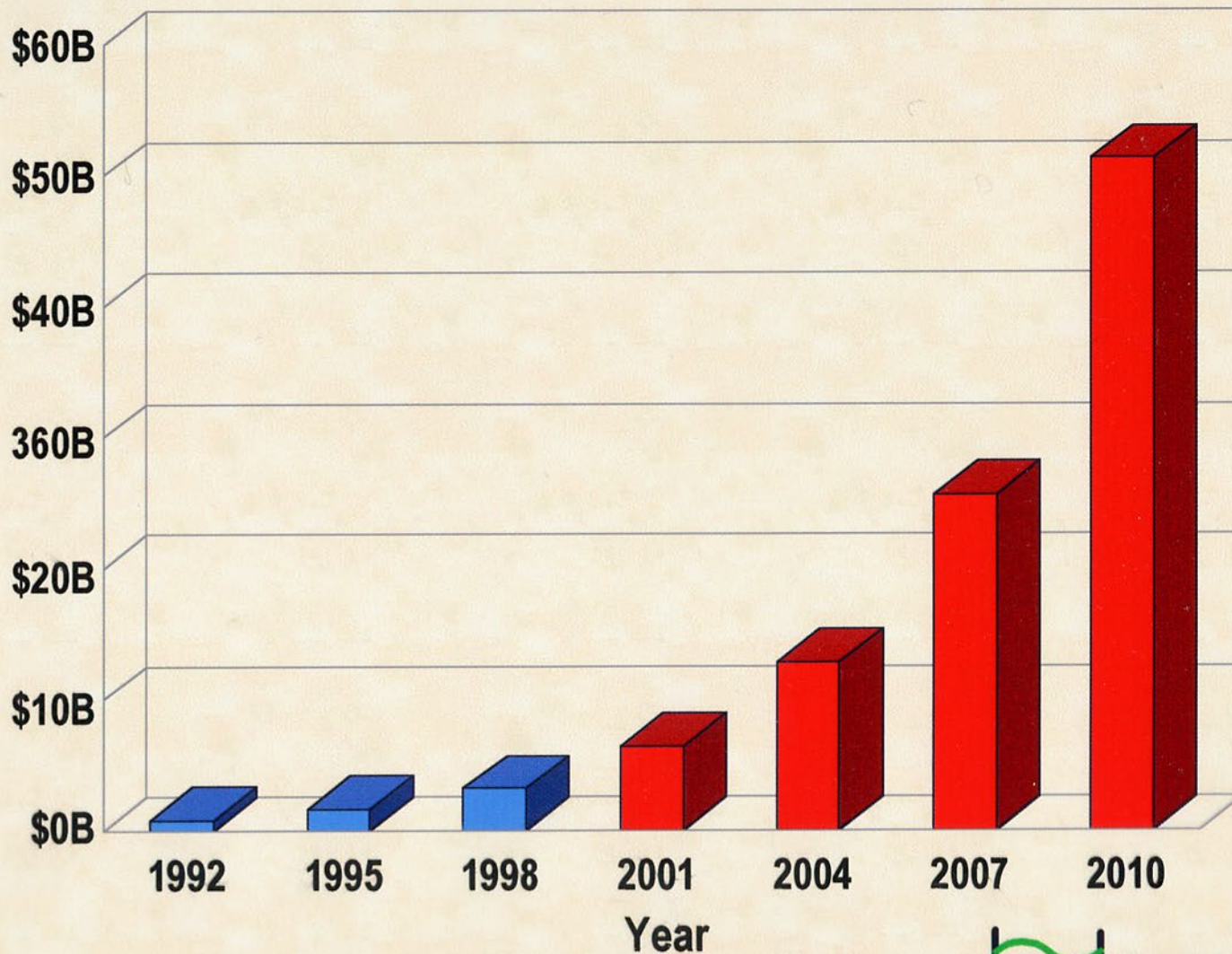
- Bottom Up:

Assemble nanoscale object using even smaller units (atoms and molecules)

Ultimate Goal: “Dial in” properties that you want by designing and building at the scale of nature (i.e. the nanoscale)

Moore's Second Law

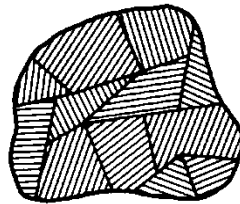
Cost of Fab



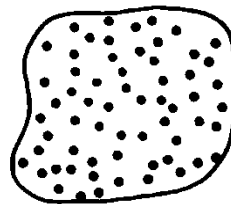


What is a Semiconductor?

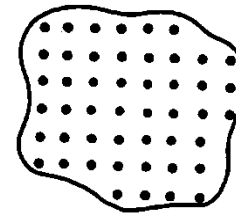
- Low resistivity \Rightarrow “conductor”
- High resistivity \Rightarrow “insulator”
- Intermediate resistivity \Rightarrow “semiconductor”
 - conductivity lies between that of conductors and insulators
 - generally crystalline in structure for IC devices
 - In recent years, however, non-crystalline semiconductors have become commercially very important



polycrystalline



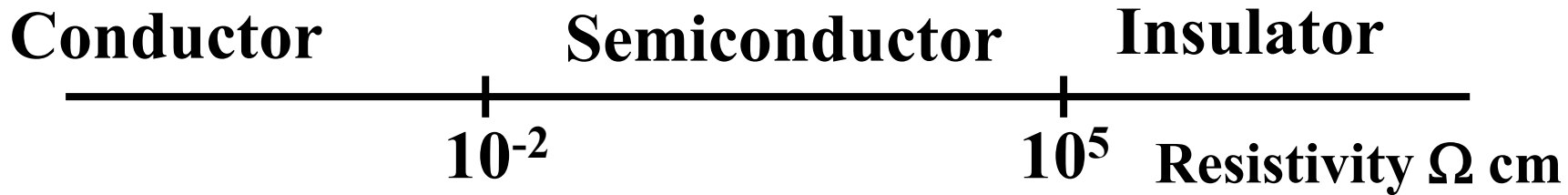
amorphous



crystalline



Semiconductor



Examples:

- Aluminum = $10^{-6} \Omega$ cm
- $\text{SiO}_2 = 10^{16} \Omega$ cm

Dopant concentration

- Electron (hole) concentration \rightarrow n (p)



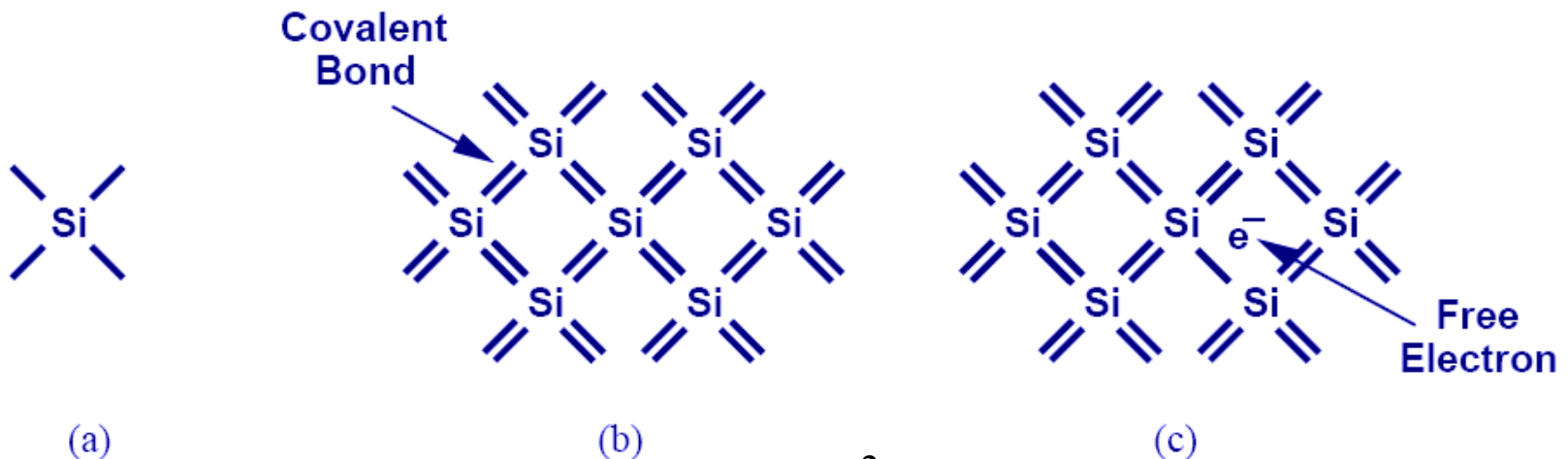
Semiconductor Materials

	III	IV	V	
	Boron (B)	Carbon (C)		
• • •	Aluminum (Al)	Silicon (Si)	Phosphorous (P)	• • •
	Galium (Al)	Germanium (Ge)	Arsenic (As)	
		• • •		



Silicon

- Atomic density: 5×10^{22} atoms/cm³
- Si has four valence electrons. Therefore, it can form covalent bonds with four of its nearest neighbors.
- When temperature goes up, electrons can become free to move about the Si lattice.



Intrinsic Si $n_i = 3.87 \times 10^{16} T^{\frac{3}{2}} \exp\left[\frac{-7014}{T}\right]$
 1.45×10^{10} at room temperature



Electronic Properties of Si

- **Silicon is a semiconductor material.**
 - Pure Si has a relatively high electrical resistivity at room temperature.
- **There are 2 types of mobile charge-carriers in Si:**
 - **Conduction electrons** are negatively charged;
 - **Holes** are positively charged.
- **The concentration ($\#/cm^3$) of conduction electrons & holes in a semiconductor can be modulated in several ways:**
 1. **by adding special impurity atoms (*dopants*)**
 2. **by applying an electric field**
 3. **by changing the temperature**
 4. **by irradiation**



Doping (N type)

- Si can be “doped” with other elements to change its electrical properties.
- For example, if Si is doped with phosphorus (P), each P atom can contribute a conduction electron, so that the Si lattice has more electrons than holes, *i.e.* it becomes “N type”:



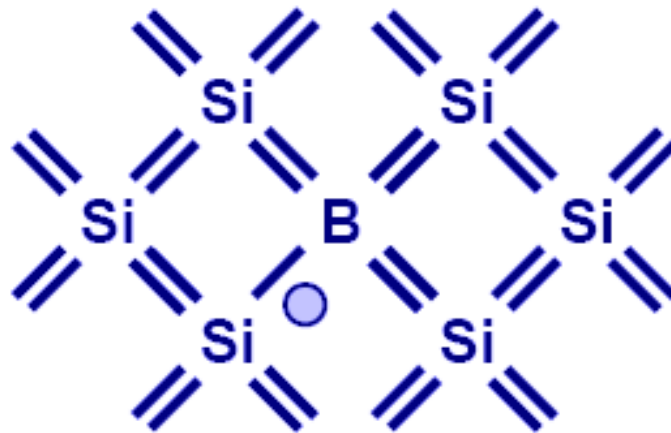
Notation:

n = conduction electron
concentration



Doping (P type)

- If Si is doped with Boron (B), each B atom can contribute a hole, so that the Si lattice has more holes than electrons, *i.e.* it becomes “P type”:



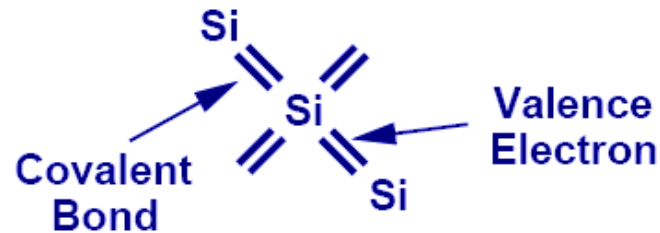
Notation:

p = hole concentration



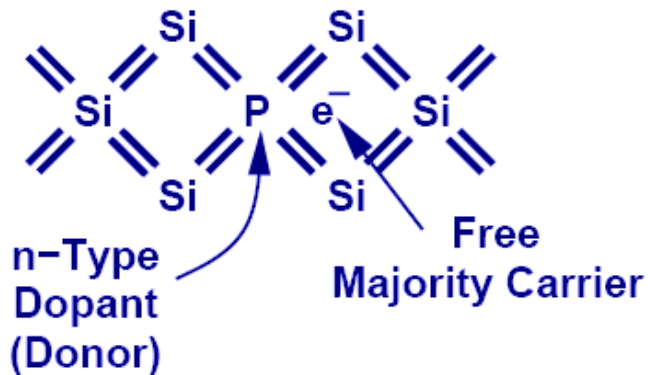
Charge Carriers

Intrinsic Semiconductor

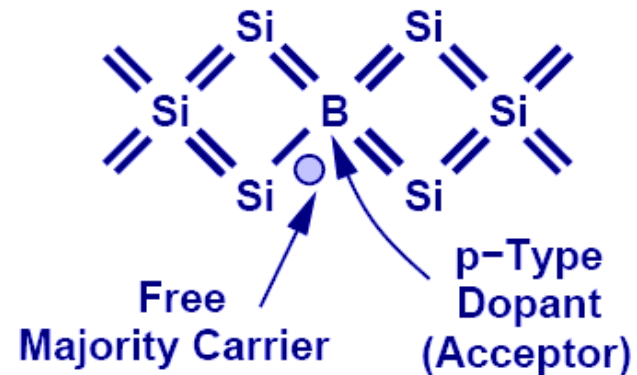


Extrinsic Semiconductor

Silicon Crystal
 N_D Donors/cm³



Silicon Crystal
 N_A Acceptors/cm³





Electron and Hole Concentrations

- Under thermal equilibrium conditions, the product of the conduction-electron density and the hole density is ALWAYS equal to the square of n_i :

$$np = n_i^2$$

N-type material

$$n \approx N_D$$

$$p \approx \frac{n_i^2}{N_D}$$

P-type material

$$p \approx N_A$$

$$n \approx \frac{n_i^2}{N_A}$$



Terminology

donor: impurity atom that increases n

acceptor: impurity atom that increases p

N-type material: contains more electrons than holes

P-type material: contains more holes than electrons

majority carrier: the most abundant carrier

minority carrier: the least abundant carrier

intrinsic semiconductor: $n = p = n_i$

extrinsic semiconductor: doped semiconductor



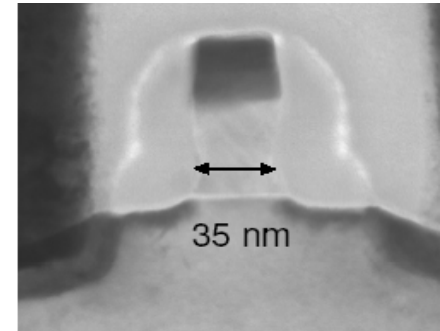
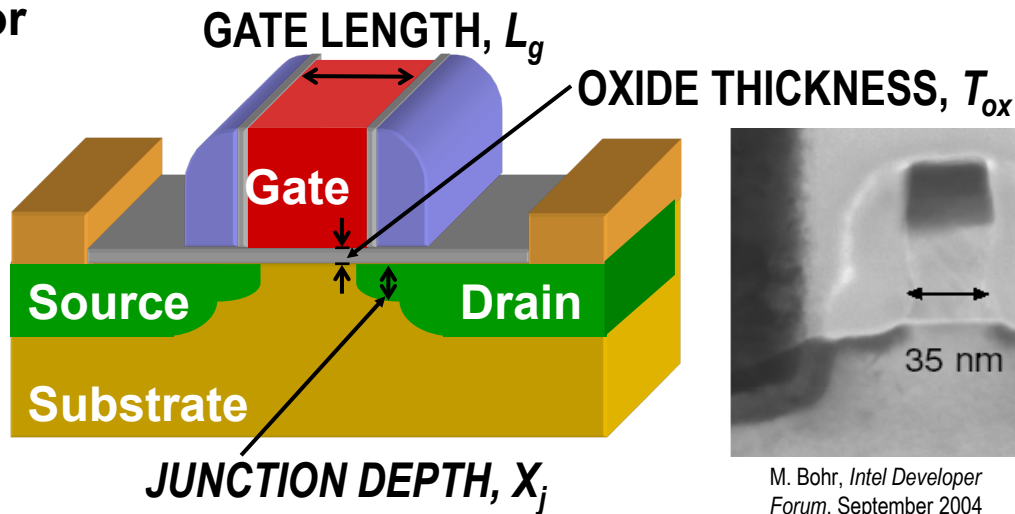
Facts

- The band gap energy is the energy required to free an electron from a covalent bond.
 - E_g for Si at 300K = 1.12eV
- In a pure Si crystal, conduction electrons and holes are formed in pairs.
 - Holes can be considered as positively charged mobile particles which exist inside a semiconductor.
 - Both holes and electrons can conduct current.
- Substitutional dopants in Si:
 - Group-V elements (*donors*) contribute conduction electrons
 - Group-III elements (*acceptors*) contribute holes



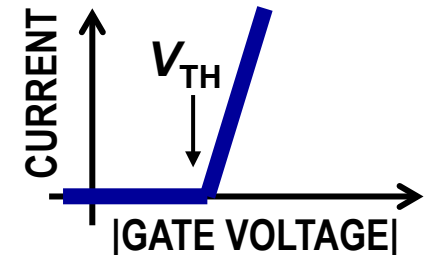
The MOSFET

Metal-Oxide-Semiconductor
Field-Effect Transistor:



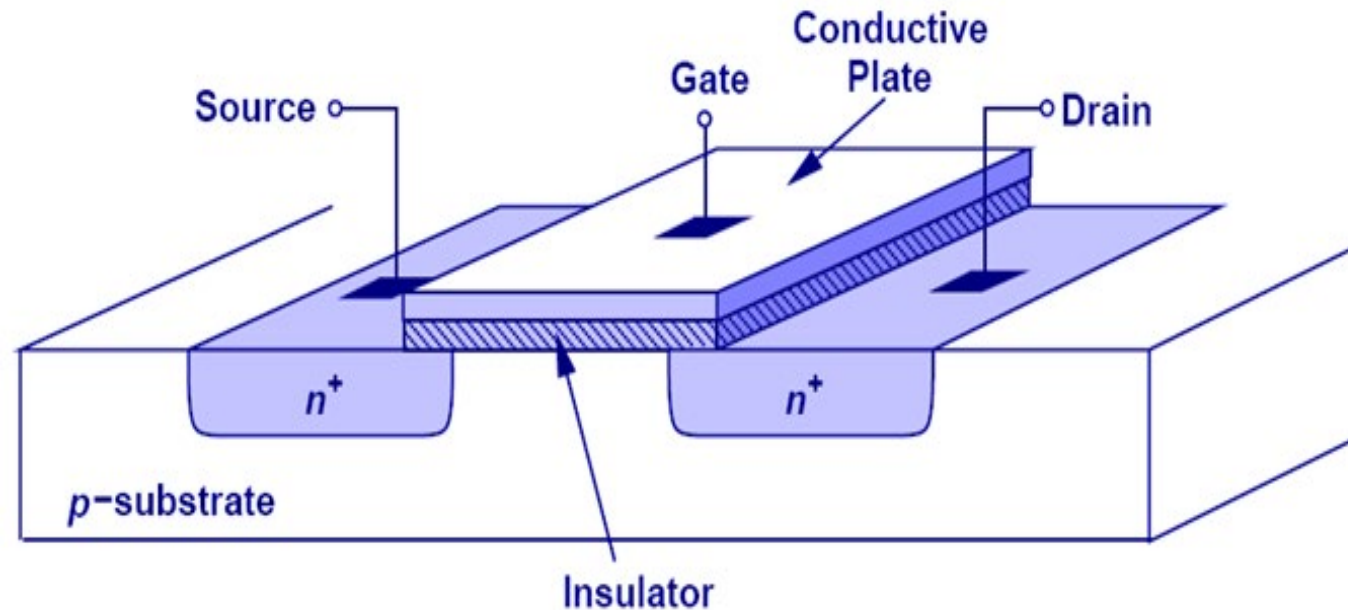
M. Bohr, Intel Developer Forum, September 2004

- Current flowing through the **channel** between the **source** and **drain** is controlled by the **gate** voltage.
- “N-channel” & “P-channel” MOSFETs operate in a complementary manner
“CMOS” = Complementary MOS

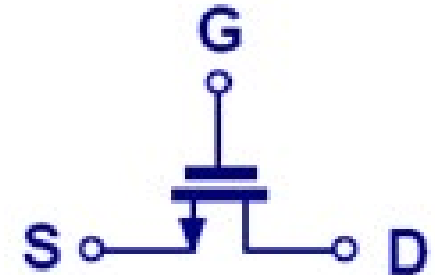




N-Channel MOSFET Structure



Circuit symbol



- The conventional gate material is heavily doped polycrystalline silicon (referred to as “polysilicon” or “poly-Si” or “poly”)
 - Note that the gate is usually doped the same type as the source/drain, *i.e.* the gate and the substrate are of opposite types.
- The conventional gate insulator material is SiO_2 .
- To minimize current flow between the substrate (or “body”) and the source/drain regions, the p-type substrate is grounded.



HW#1 – Problem 2&3

Problem 2 (Sensitivity)

We discussed about the “hot-wire” sensor in class without going into detail analyses. Let’s assume that using micro-machining processes, we can make a “hot-wire” sensor of $1\mu\text{m}$ in diameter and $5\mu\text{m}$ in length. While if we use nano-machining process, one can make a “hot-wire” sensor of 1nm in diameter and $5\mu\text{m}$ in length. If the materials properties in both cases are the same, you are asked to calculate the ratio of sensitivity for the two cases – please make all necessary other assumptions.

Problem 3 (DNA)

We mentioned DNA briefly in the class and this is a follow-up question. A host on a radio program stated that one gram of DNA has the ability to store as much information as 1 trillion CDs. Is this true? (Please specify the foundations/assumptions of your calculations)



HW#1 – Problem 4

Problem 4 (MOSFET)

The diagram shows a standard MOSFET. (1) Draw the cross-sectional view diagram in the areas under the two dash lines. (2) Assuming that the drawing is in scale and the minimum feature size is 45nm for the gate length. Calculate how many MOSFET can be placed in an area of 1" x 1"

